

Supplementary Data

Influence of CH₄-Ar ratios on composition, microstructure and optical properties of Be₂C films synthesized by DC reactive magnetron sputtering

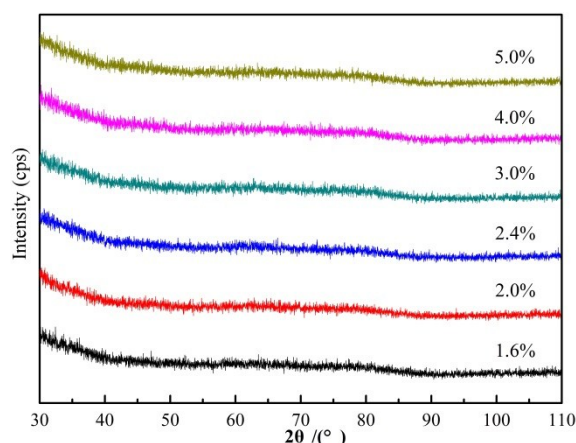
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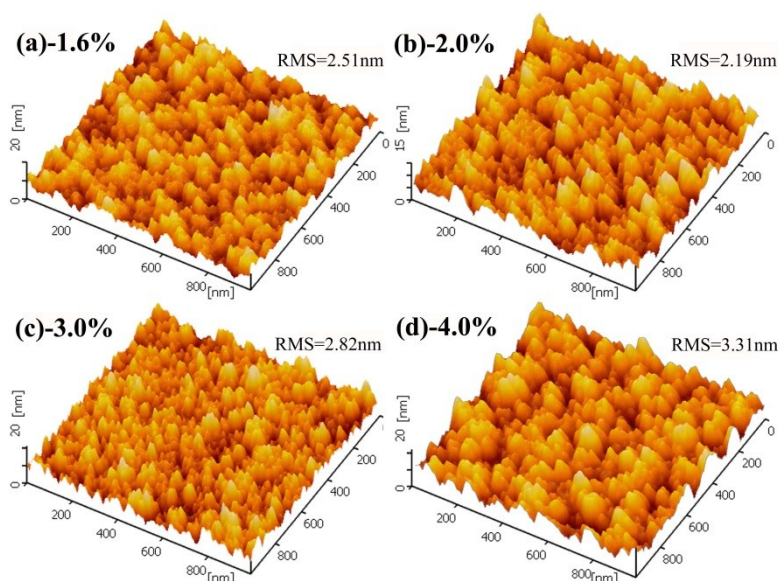
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Supplementary Data Fig. S1 | XRD patterns of as-deposited Be₂C films prepared at various CH₄-Ar ratios.



Supplementary Data Fig.S2 | Surface morphologies (AFM 3-dimension images) of the Be₂C films deposited at (a) 1.6%, (b) 2.0%, (c) 3.0% and (d) 4.0% CH₄-Ar ratios and their corresponding RMS

roughness.